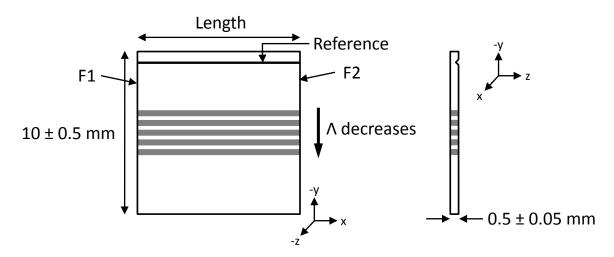
Device Specification MSHG1180-0.5-xx



[Image for reference only. Not to scale.]

Description MgO doped PPLN SHG crystal for 1180nm pump

Thickness(z) 0.5mm±0.05mm

Width(y) 10mm±0.5mm

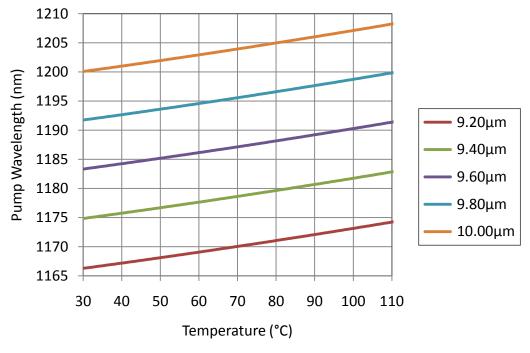
Length(x) 20mm±0.5mm, 10mm±0.2mm, 5mm±0.1mm

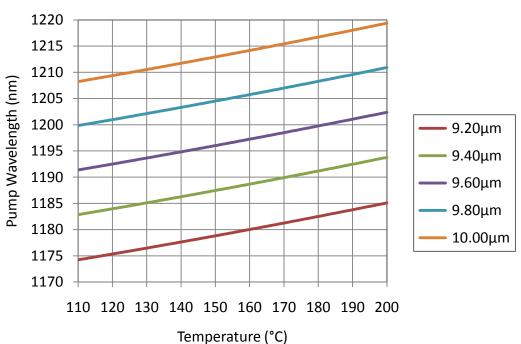
Periods(Λ) 9.20, 9.40, 9.60, 9.80, 10.00μm

NOTES:

- The SHG device material is Magnesium doped Lithium Niobate with five periodically poled gratings. Each grating is 0.5mm wide with individual periods as listed above. A saw-cut reference mark is provided on the +z face of the crystal to determine the largest grating period (see above diagram). Each poled grating is separated by 0.2mm wide regions of unpoled material.
- 2 The average mark-to-space ratio of each grating is better than 70:30.
- 3 Each device is etched to make the poled gratings visible. Due to the wet-etch nature of this process the top and bottom surface finish of each device may appear cloudy or uneven.
- 4 Perpendicularity of input/output facets F1 and F2 to gratings is within ±0.15°. Parallelism between end facets F1 and F2 is within ±5 minutes.
- Optical finish of facets F1 and F2 is within 20/10 scratch dig with $\lambda/8@1064$ nm. No more than two 100 μ m size chips per end facet.
- 6 Dual coating to less than R<1% at 590 & 1180nm on both input/output facets.

Device Specification MSHG1180-0.5-xx





For more information, please contact us at:

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